



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the Application of

Shunichi SEKI et al.

Group Art Unit: 1762

Application No.: 09/701,534

Examiner: M. Cleveland

Filed: November 30, 2000

Docket No.: 107291

For: METHOD FOR FORMING SILICON FILM AND INK COMPOSITION FOR INK JET

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed before the mailing date of a first Office Action on the merits after the filing of a Request for Continued Examination under 37 CFR §1.114. No certification or fee is required.
- ☒ 2. English-language Abstracts of the non-English language references are attached.
- ☒ 3. Computer-generated English translations of the Japanese Patent Publications for references 3 and 5 have been obtained from the website of the Japanese Patent Office ([<http://www.jpo.go.jp>]), and are attached, but have not been reviewed for accuracy.
- ☒ 4. Reference 5 was forwarded by an Information Disclosure Statement filed November 30, 2000. However, a translation was not provided at that time as such was not reasonably available.

Respectfully submitted,

James A. Oliff
Registration No. 27,075

Gerhard W. Thielman
Registration No. 43,186

JAO:GWT/gwt

Date: July 29, 2004

OLIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400

**DEPOSIT ACCOUNT USE
AUTHORIZATION**

Please grant any extension
necessary for entry;
Charge any fee due to our
Deposit Account No. 15-0461

Sheet 1 of 1

Form PTO-1449 (REV. 8-83)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 107291		APPLICATION NO. 09/701,534	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANT(S) Shunichi SEKI et al.			
				FILING DATE November 30, 2000		GROUP 1762	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	
	1	GB 2 077 710 A	12/23/1981	Great Britain			
	2	JP-A 64-029661 w/ Abstract	01/31/1989	Japan			
	3	JP-A 09-237927 w/ Abstract and translation	09/09/1997	Japan			
	4	JP-A 63-111454 w/ Abstract	05/16/1988	Japan			
	5	JP-A 10-321536 w/ Abstract and translation	12/04/1998	Japan			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)							
	6	"Advances in deposition Processes for Passivation Films", W. Kern <i>et al.</i> , <i>J. Vac. Sci. Technology</i> , 14 , 1082, ©1977.					
	7	"Substitutional doping of Amorphous Silicon", W. E. Spear <i>et al.</i> , <i>Solid State Communications</i> , 17 , 1193, ©1975.					
EXAMINER					DATE CONSIDERED		
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

Date: July 29, 2004